

# Developments Toward a Rapidly Tunable RF Cavity at FAR-TECH, Inc.

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#### Acknowledgement

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This problem was suggested to us by Dr. A. Sessler.



#### **Motivation**

Rapid-Cycling Accelerators (synchrotron, FFAG) have varying revolution times on successive orbits, requiring different accelerating cavity frequency for each cycle.

The short time required of adjusting the accelerating cavity frequency became a bottleneck for the development of such accelerators.

- These revolution times can be as low as 100 ns
- Ferromagnetic (ferrite) tuning cannot adjust the frequency of the cavity rapidly enough
- Low Q solutions (magnetic alloy or high external Q) waste RF power

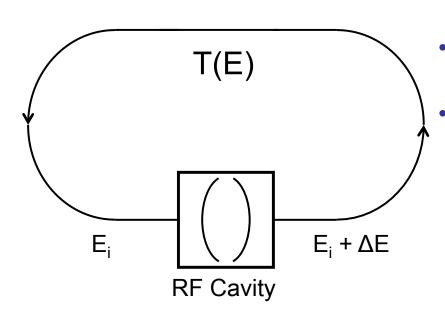


#### **Motivation - continued**

- Ferroelectric material in accelerator applications have shown response times < 10ns</li>
- FAR-TECH is developing a ferroelectric tuned cavity in the frequency range 375 – 400 MHz as a start.
- Potential uses include proton/C<sup>6+</sup> ion cancer therapy and subcritical reactors



#### The Problem in a Nutshell

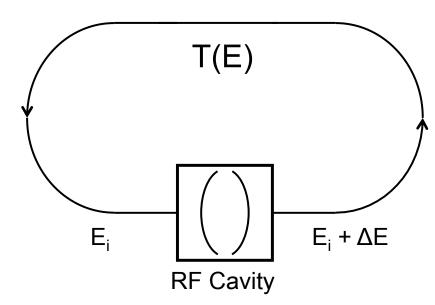


- Want φ<sub>rf</sub> /2π to be an integer for oncrest acceleration
  - For fixed frequency, this only happens if *f* is a harmonic of 1/T
- This makes fixed frequency acceleration difficult if T changes (which it does)

Cartoon Schematic of a Generic Recirculating Accelerator



#### The Problem in a Nutshell



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- Want φ<sub>rf</sub>/2π to be an integer for oncrest acceleration
- For fixed frequency, this only happens if *f* is a harmonic of 1/T
- This makes fixed frequency acceleration difficult if T changes (which it does)
- For *changing* frequency, adjust f(t) such that the phase change between crossings ( $\phi_{rf}/2\pi$ ) is an integer
- The time history of the frequency is just as important as the size of the change in frequency over the revolution

$$\frac{\varphi_{rf}}{2\pi} = \int_{t_i}^{t_i+1} f(t) dt$$



## Low Q vs. "Higher" Q RF Cavity

- Low Q RF Cavity (Q ~ 2-500)
  - Wide resonance implies
    - Stored RF energy is "dumped" between cavity crossings
    - Greater RF losses
    - Generally does not require active tuning
  - Short fill time allows for replacement of RF power between cavity crossings
- "Higher" Q RF Cavity (Q > 1000)
  - Must be actively tuned
  - Narrow resonance implies lower RF losses
  - Stored energy is "conditioned" and remains in the cavity for many cycles
  - To maintain stable power levels, the RF power feed must be synchronous in both frequency and phase with the stored energy in the cavity



#### Ferroelectrics (FE) are the key

Ferroelectric materials change permittivity (ε) when exposed to a biasing electric field and can have low loss tangent

- ε changes with changing electric field bias
- Base ε values between 75 and 800 are possible
- Low loss tangent does not mean low losses due to high ε
   Loss ∝ ε tanδ
- Material properties do not allow for high ε tuning and low loss tangent simultaneously
- Material response time < 10 ns (limit of manufacturer's testing)</li>



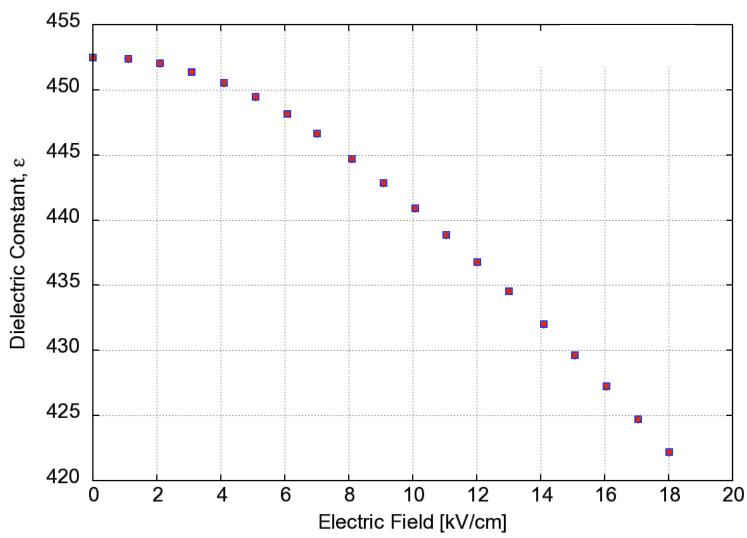
#### Ferroelectrics (FE) are the key - continued

- Ferroelectric tuning is directly analogous with ferrite tuning
  - Permittivity (permeability) change results in a frequency shift
  - Strength of the effect is based on the fraction of electric (magnetic) RF field stored energy in the material.
  - Losses are associated with the stored energy in the material and the electric (magnetic) loss tangent
  - Heat mitigation is a primary concern
- The effect of a large change in the dielectric constant results in non-linear perturbation of the RF field patterns



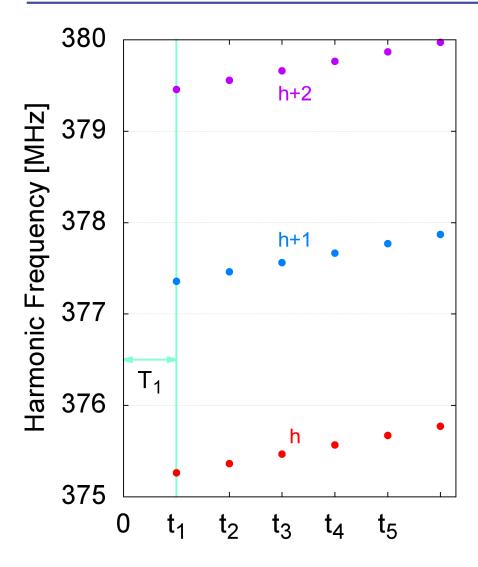
#### **Characteristics of Ferroelectric Material**

#### **Dielectric Constrant Based on Measured Data**





## **Harmonic Number Ratcheting**



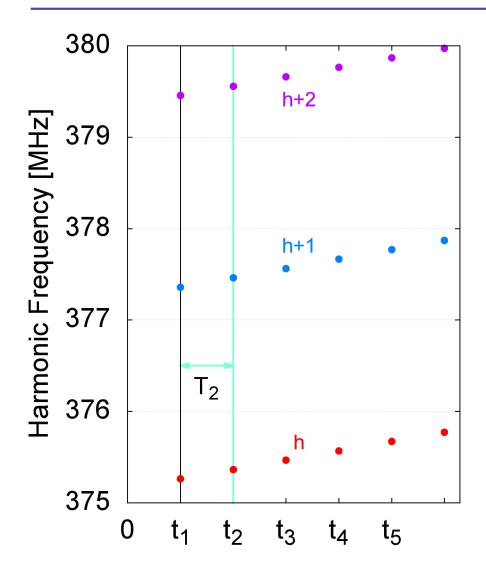
Consider a case: (h= harmonic number)

At  $t=t_1$ , orbit time is  $T_1$ If h = 100,  $f_{100} = 100 / T_1$ If h = 101,  $f_{101} = 101 / T_1$ If h = 102,  $f_{102} = 102 / T_1$ 

At  $t=t_2$ , orbit time is  $T_2$ If h = 100,  $f_{100} = 100 / T_2$ If h = 101,  $f_{101} = 101 / T_2$ If h = 102,  $f_{102} = 102 / T_2$ 



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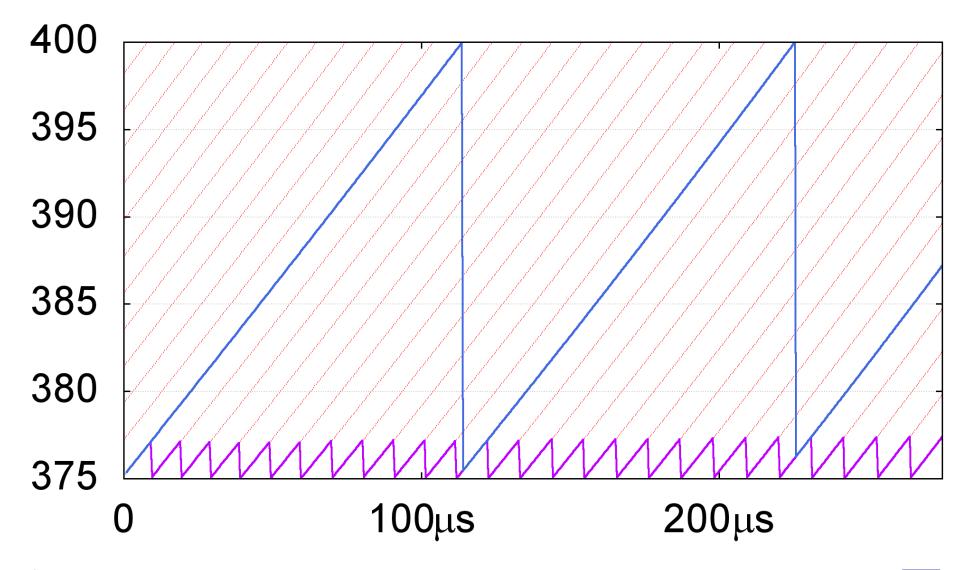
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## Harmonic Number Ratcheting - continued





#### A tunable cavity design by FAR-TECH, Inc.

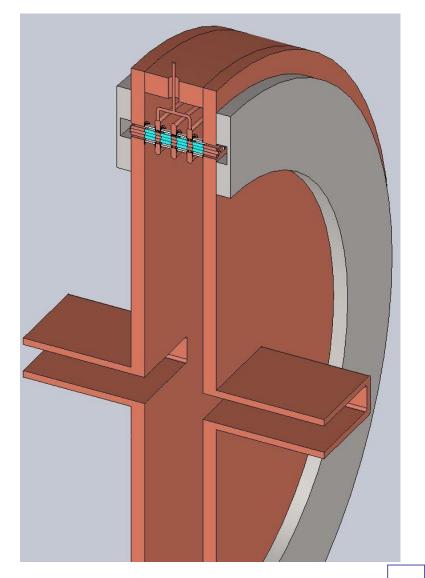
For  $\Delta f_{\text{full bias}}$  = 25 MHz, the estimated (realistic) phase shift is 0.3 $\pi$  in 150 ns

Cartridge is placed in low E<sub>RF</sub> region

The biasing scheme requires careful considerations

- Bias is not DC
- Bias load is a capacitor, with stray and fixed inductance
- Without an energy conserving scheme, bias power loss could be as high as 1 MW

Cooled cartridge is separated from the cavity vacuum.





## Tunable cavity design parameters

Property	Unbiased case	Biased case
Permittivity	ε = 450	ε = 322
Frequency (MHz)	376	400
Q-Factor	3970	5890
Copper Losses (W)	3640	2070
Ferroelectric Losses (W)	4200	1510
Total Losses (W)	7840	3580
Energy Gain (β = 0.4) (keV)	30	30
RF Energy Stored in Vacuum (mJ)	6.8	6.2
RF Energy Stored in Ferroelectric (mJ)	6.3	2.1
ZTT (MΩ/m)	0.57	1.26
r/Q (Ω)	29.0	42.7

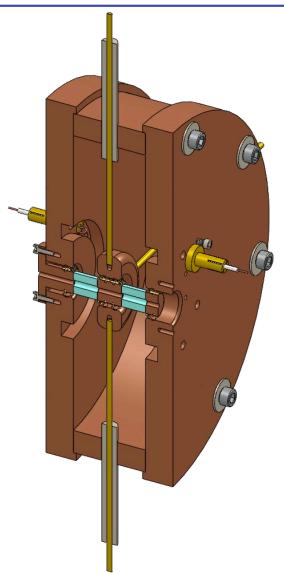
For an unloaded pillbox cavity (no beam pipe) of the same radius:

$$f = 428.9 \text{ MHz}$$

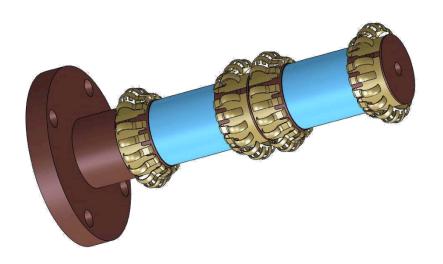
$$Q = 22800$$



#### **Cold Test Cell for Basic Verification Studies**



- Placed the cartridge in center
- Test construction details
  - Contact spring
  - Solder joints
  - Test FE coating technique
- Cavity Q measurements



### **Cold Test Without Cartridge**



	Fundamental	Quadrupol e
f <sub>meas</sub> (MHz)	1809.3	3830.1
f <sub>HFSS</sub> (MHz)	1809.6	3834.6
Q <sub>meas</sub>	10800	14700
Q <sub>HFSS</sub>	12820	18008
	$\overline{}$	

Due to joint resistance in bolted cavity

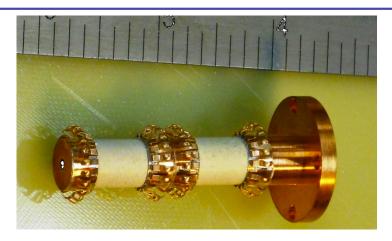
~375 MHz w cartridge

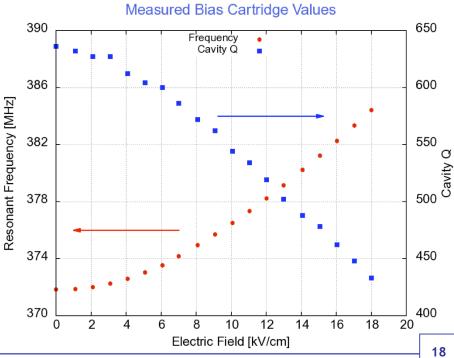


#### Cartridge Cold Test with Network Analyzer



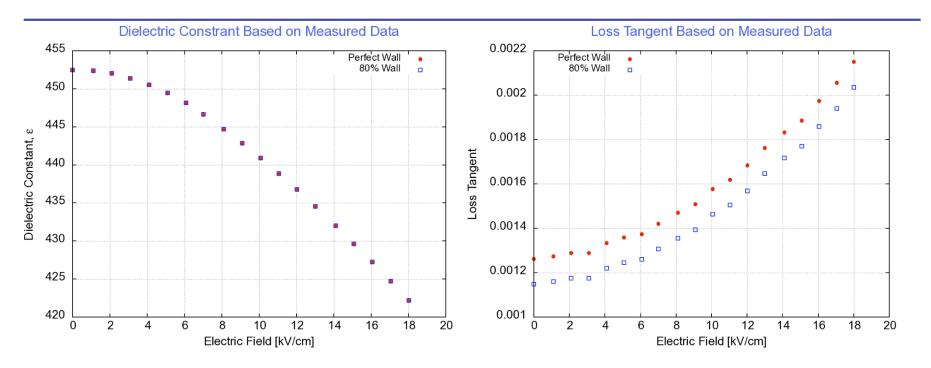
- Transformer oil needed inside tube to reduce arcing
- DC electric field bias inferred from voltage and 1cm FE length







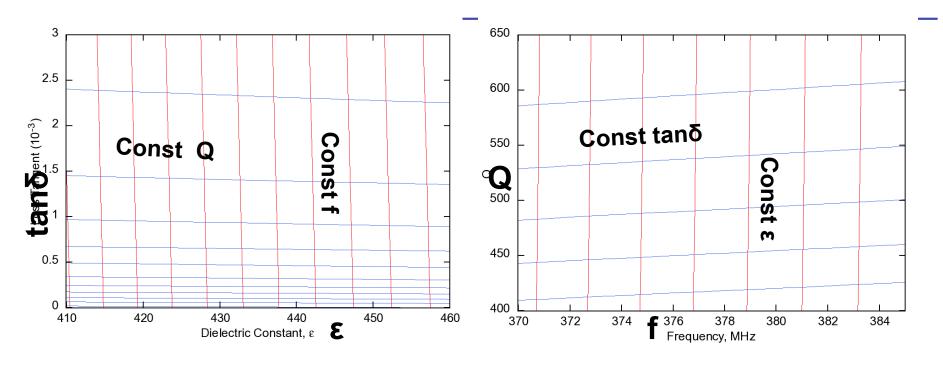
#### ε and tanδ from Cold Test Data



- FE losses from tanδ only termination effects folded into bulk losses
- HFSS simulations to determine (f,Q) from (ε, tanδ)
- $Q = Q_{wall} || Q_{FE}$ 
  - Reduction of Q<sub>wall</sub> to 80% HFSS value to account for contact losses
- Use simulation data to determine ( $\epsilon$ , tan $\delta$ ) from measured (f,Q) cubic spline interpolation



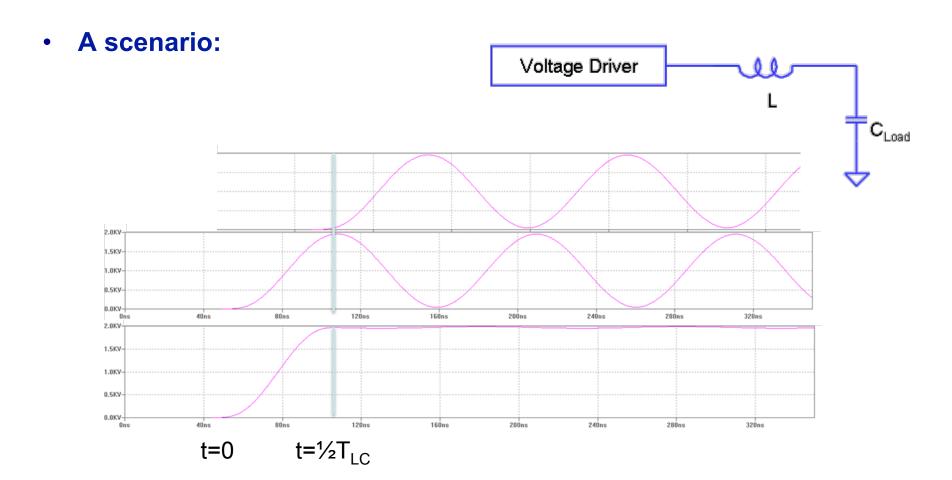
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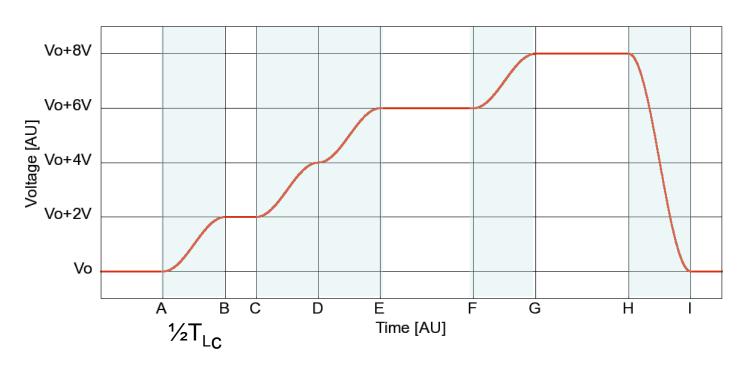


## **Biasing the Cartridge**





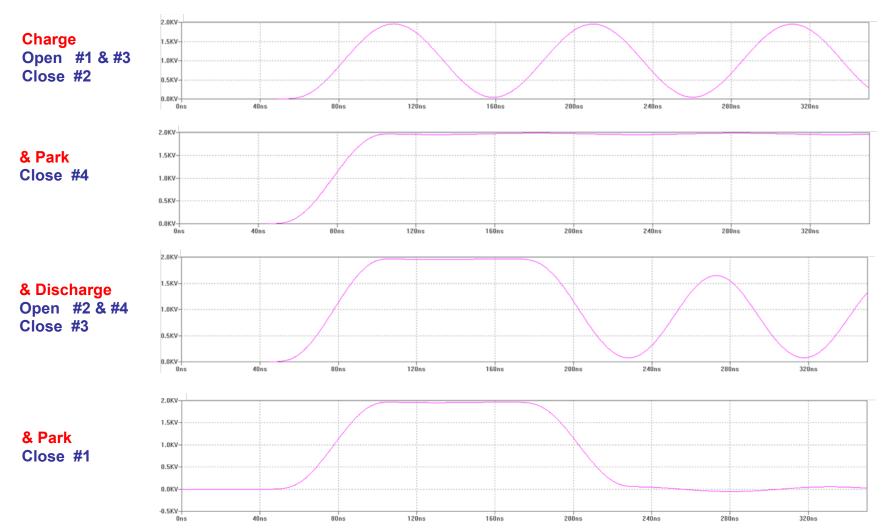
## A Scenario of Voltage Ramp on C<sub>Load</sub>



Scenario with 4-voltage sources
Delay between (dis)charge and park (shaded) is ½T<sub>LC</sub>
Arbitrary delay between park and next (dis)charge



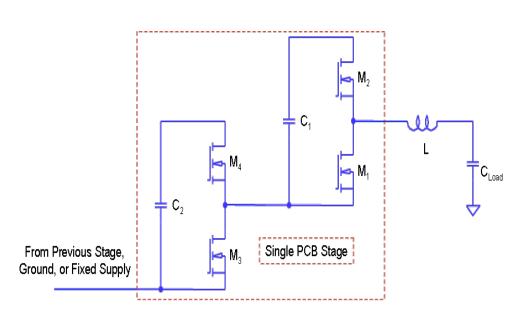
### **Spice Simulation – Results**

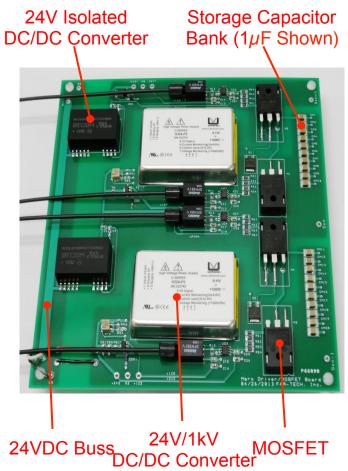


Imperfect "flat" parking due to switching energy loss, and resulting miss-match in voltages between stages and load



## **Bias Voltage Switching Circuit Board**

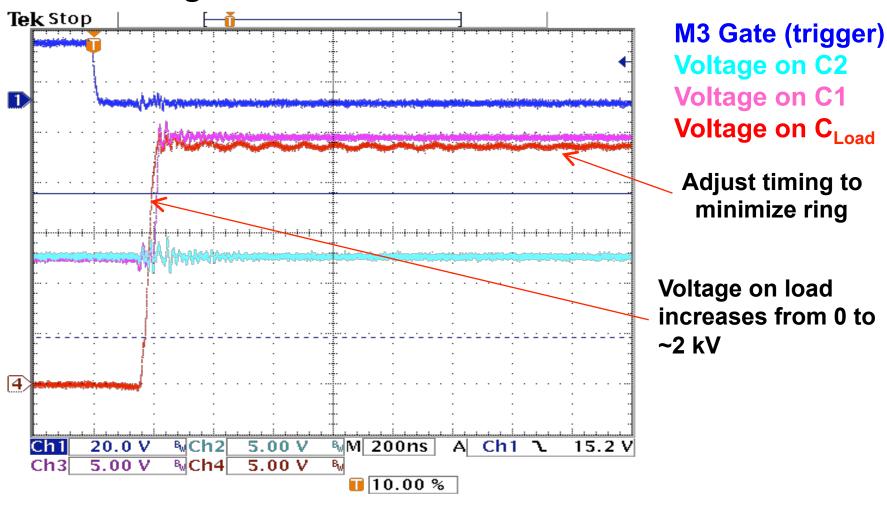






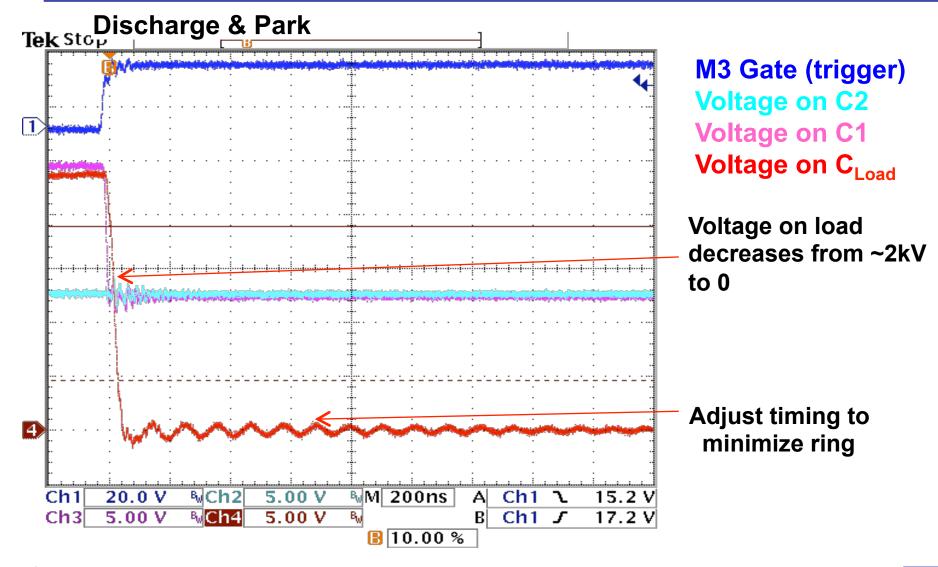
## 2 kV Testing with Fixed C<sub>Load</sub> -- Charge

#### **Charge & Park**



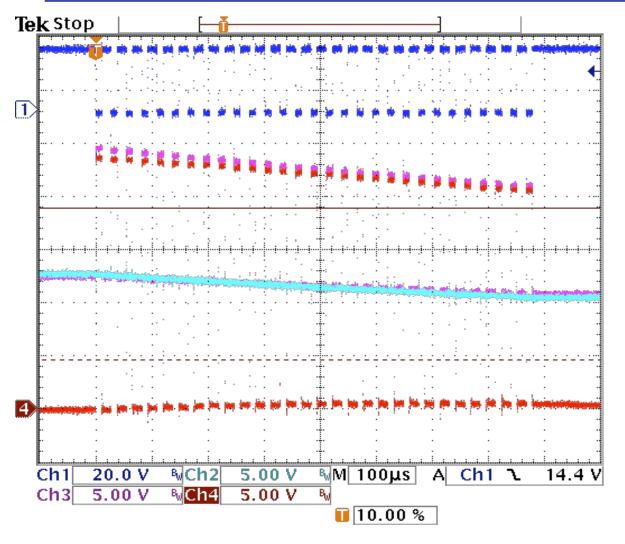


## 2 kV Testing with Fixed C<sub>Load</sub> – Discharge



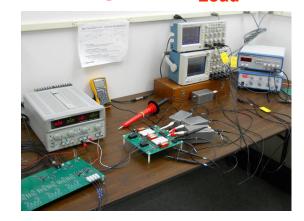


## 2 kV Testing with Fixed C<sub>Load</sub> – Losses



M3 Gate (trigger)

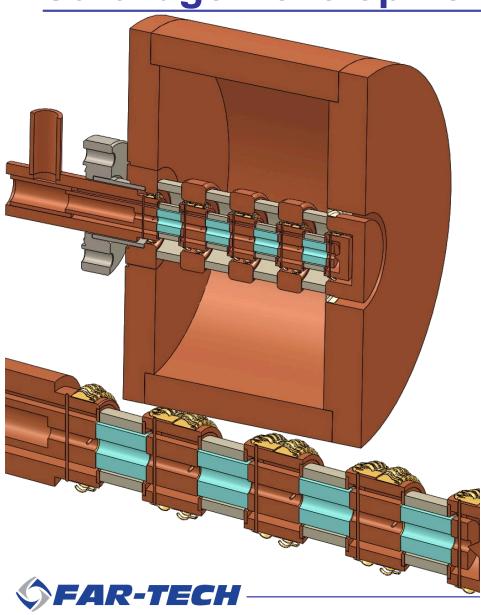
Voltage on C2
Voltage on C1
Voltage on C<sub>Load</sub>



Multiple pulses with deliberately reduced storage capacitance enhances the effect of losses for measurement and determines charging requirements



## High Power Equivalent Test Cell for Cartridge Development (work in progress)



- The goal is to determine maximum possible RF electric field on the FE and study hysteresis effects
- Place cartridge on axis:
  - Concentrates RF electric field
  - RF power reduced for same RF field in the FE as seen in a real accelerating cavity
- FE is cooled with dielectric fluid in a series flow
- Vacuum, and dielectric fluid coolant are separated by outer layer of Al<sub>2</sub>O<sub>3</sub>
- Cartridge is removable under vacuum operation – major advantage
- Complicated construction process, many issues are under investigation

#### Conclusion

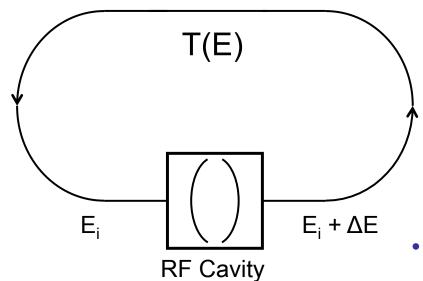
- Ferroelectric cartridge has potential for rapidly tunable cavity.
- Rapidly tunable cavity opens up new lattice design possibilities that have not been fully explored
- Cold tests of the 2-cell cartridge performed.
  - Inferred ε and tanδ from measured f and Q as function of bias V
- DC Voltage control and fast switching fabricated. Tested up to 2KV in 55 nsec.

#### Next step: ----

4-cell cooled cartridge in vacuum cavity with 8 kV pulser 55 nsec (50 pC load)



#### A message ...



$$\frac{\varphi_{rf}}{2\pi} = \int_{t_i}^{t_i+T} f(t) dt$$

- For *changing* frequency, adjust f(t) such that the phase change between crossings ( $\phi_{rf}/2\pi$ ) is an integer
- Required tunability could be less than what we thought



Fusion and Accelerator Research and Technology, San Diego CA

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